

IN THE ABSTRACT

Please cancel the current abstract and insert the following. A marked-up copy showing the changes made to the abstract is attached hereto in Appendix A.

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21 A charged particle beam exposure system which draws a pattern on an object to be exposed by a plurality of charged particle beams emitted from a plurality of element electron optical systems includes (a) a storage device storing (i) a standard dose data for controlling the irradiation of charged particle beams to an object to be exposed, (ii) plural pieces of proximity effect correction data for correcting the irradiation of the charged particle beams for each incidence position with respect to the object to be exposed, in order to reduce the influence of a proximity effect, and (iii) calibration data for correcting variations in the irradiation dose among the plurality of the charged particle beams emitted from the plurality of element electron optical systems, and (b) a controller for controlling the irradiation of each of the charged particle beams, based on the standard dose data, the proximity effect correction data, and the calibration data. ~

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IN THE SPECIFICATION:

Please amend the specification as follows:

Please substitute the paragraph beginning at page 7, line 25, and ending on page 8, line 3, with the following. A marked-up copy of this paragraph, showing the changes made thereto, is attached in Appendix A.